

IN THE SPECIFICATION

Please amend paragraph 26 as follows:

As will be explained in more detail below, brush enclosure 212 also includes open region 222 and, in one embodiment, additionally includes two opposing flanges 214 that extend along length and side of open region 222. Brush enclosure 212 is comprised of a chemically inert material. Exemplary chemically inert materials include plastic, ~~Delrin~~, DELIRINTM (polyoxymethylene) polyvinylidene fluoride (PVDF), polyethylene terephthalate (PET), etc.

Please amend paragraph 34 as follows:

The liquid used to generate foam ~~340~~ 410 is a liquid or any combination of liquids that will chemically react or will facilitate a chemical reaction when placed in direct contact with another material. The liquid may be a semi-aqueous or aqueous solution of deionized water (DIW) containing suitable cleaning fluids. Examples of liquids include water (H₂O); deionized water (DIW); water (H₂O) and cleaning fluid; water (H₂O) and surfactant; water (H₂O), cleaning fluid, and surfactant; deionized water (DIW) and surfactant; and deionized water (DIW), cleaning fluid and surfactant. As discussed above, an embodiment of the present invention uses water as the liquid because water enables or facilitates the chemical reaction between ozone and an organic photoresist material. For more details on foam generation and cleaning substrate 216 using foam 410, reference may be made to a U.S. Patent Application No. 10/608,871 entitled "Method and Apparatus for Removing a Target Layer from a Substrate Using Reactive Gases," which is herein incorporated by reference.